

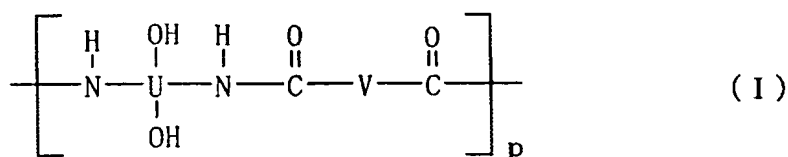
AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

1. (Original) A photosensitive polymer composition comprising:

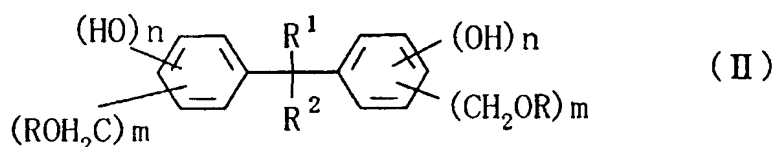
(a) a polyamide having a repeating unit represented by the following general formula (I):



wherein U represents a tetravalent organic group, V represents a bivalent organic group and p is an integer representing a number of the repeating unit;

(b) a compound which generates an acid upon receiving light; and

(c) a compound represented by the following general formula (II):



wherein m and n are each independently integer of 1 or 2, Rs are each independently hydrogen, alkyl group or acyl group, and R¹ and R² each independently represents fluoroalkyl group having 1 to 3 carbon atoms.

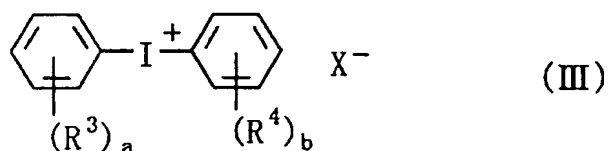
2. (Original) The photosensitive polymer composition according to claim 1, wherein the compound represented by the general formula (II) is 2,2-bis[3,5-bis(hydroxymethyl)-4-hydroxyphenyl]-1,1,1,3,3,3-hexafluoropropane.

3. (Original) The photosensitive polymer composition according to claim 1, wherein the compound represented by the general formula (II) is 2,2-bis[3,5-bis(methoxymethyl)-4-hydroxyphenyl]-1,1,1,3,3,3-hexafluoropropane.

4. (Currently amended) The photosensitive polymer composition according to claim 1 ~~any one of claims 1 to 3~~, wherein ratios of the component (b) and the component (c) are 5 to 100 parts by weight and 1 to 30 parts by weight, respectively based on 100 parts by weight of the component (a).

5. (Currently amended) The photosensitive polymer composition according to claim 1 ~~any one of claims 1 to 3~~ further comprising (d) a compound which reduces a solubility of the component (a) with respect to an alkali aqueous solution.

6. (Original) The photosensitive polymer composition according to claim 5, wherein the component (d) is a diaryliodonium salt represented by the following general formula (III):



wherein X^- represents counteranion, R^3 and R^4 each independently represents alkyl group or alkenyl group, and a and b are each independently integer of 0 to 5.

7. (Original) The photosensitive polymer composition according to claim 5, wherein ratios of the component (b), the component (c) and the component (d) are 5 to 100 parts by weight, 1 to 30 parts by weight and 0.01 to 15 parts by weight, respectively based on 100 parts by weight of the component (a).

8. (Currently amended) A method of producing a pattern comprising the steps of:

applying the photosensitive polymer composition according to claim 1~~any one of claims 1 to 3~~ on a support substrate and drying the photosensitive polymer composition;

exposing light to a photosensitive resin layer obtained by drying the photosensitive polymer composition to make a predetermined pattern;

developing the photosensitive resin layer after the exposing light; and
heat treating the photosensitive resin layer after the developing.

9. (Original) The method of producing the pattern according to claim 8, wherein an exposure light source used in the step of exposing generates i-line.

10. (Original) An electronic part comprising:
an electronic device having a layer of the pattern obtained by the method according to claim 8,

wherein the layer of the pattern is provided as an interlayer insulating film and/or a surface protection layer in the electronic device.